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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/076,976	02/15/2002	Xiangxin Bi	2950.18US02	1411	
7	590 03/06/2003				
Patterson, Thuente, Skaar & Christensen, P.A.			EXAMINER		
4800 IDS Cent 80 South 8th St		LE, HOA T			
Minneapolis, M	IN 55402-2100				
			ART UNIT	PAPER NUMBER	
			1773	<i>i</i> 1	
			DATE MAILED: 03/06/2003	()	

Please find below and/or attached an Office communication concerning this application or proceeding.

	_			AS11
•		Application No.	pplicant(s)	
Advisory Action		10/076,976	BI ET AL	
Advisory Au	- 	Examiner	Art Unit	
		H. T. Le	1773	
The MAILING DATE of th	is communication a	ppears on the cover sheet	with the correspondence add	dress
THE REPLY FILED FAILS Therefore, further action by the ap final rejection under 37 CFR 1.113 condition for allowance; (2) a timel Examination (RCE) in compliance	plicant is required to may <u>only</u> be either: y filed Notice of App	: (1) a timely filed amendm beal (with appeal fee); or (3	is application. A proper replacent which places the application.	ation in
	PERIOD FOR	REPLY [check only a) or	b)]	
reply expires on the mailing dat	of the proposed reply (we of this Advisory Action	ithin two months as set forth in I	MPEP § 706.07 (f)), the period for nailing date of the final rejection, an SIX MONTHS from the	
mailing date of the final rejection				
Extensions of time may be obtained use have been filed is the date for purpose fee under 37 CFR 1.17(a) is calculated fro (2) as set forth in (b) above, if checked. A timely filed, may reduce any earned patents.	s of determining the peri m: (1) the expiration date ny reply received by the	od of extension and the corresponds of the shortened statutory period Office later than three months at	onding amount of the fee. The app od for reply originally set in the final	ropriate extension Office action; or
1. A Notice of Appeal was filed 37 CFR 1.192(a), or any extense of the second s				
2. The proposed amendment(with requisite fees.	s) will be entered up	oon the timely submission	of a Notice of Appeal and Ap	ppeal Brief
3. The proposed amendment(s) will not be entered	d because:		
(a) they raise new issues t	hat would require fu	rther consideration and/or	search. (see NOTE below);	
(b) ⊠ they raise the issue of				
(c) they are not deemed to issues for appeal; and/o		on in better form for appea	l by materially reducing or si	mplifying the
(d) they present additiona	claims without can	celing a corresponding nu	mber of finally rejected claim	ns.
NOTE: See attachment	(DETAILED ADVISO	RY ACTION).		
4.⊠ Applicant's reply has overcor	me the following reje	ection(s): <u>all rejections unde</u>	<u>r USC 103</u> .	
5. Newly proposed or amende canceling the non-allowable		uld be allowable if submitt	ed in a separate, timely filed	amendment
6.⊠ The a) affidavit, b) exh application in condition for			een considered but does NO	T place the
7. The affidavit or exhibit will raised by the Examiner in the		because it is not directed	SOLELY to issues which we	re newly
8. For purposes of Appeal, the		s) is as follows (see attacl	hed written explanation, if an	ny):
Claim(s) allowed: None.				
Claim(s) objected to: None.				
Claim(s) rejected: <u>18-30</u> .				
Claim(s) withdrawn from co	onsideration:			
9. The proposed drawing corr	ection filed on	_ a)⊡has b)⊡ has not b	peen approved by the Exami	iner.
10. Note the attached Informat	ion Disclosure State	ment(s)(PTO-1449) Pape	er No(s)	
11. Other:			the	
			H. T. Le Primary Examiner Art Unit: 1773	

DETAILED ADVISORY ACTION

Response to Amendment

1. New matter:

The amendment filed February 17, 2003 is objected to under 35 U.S.C. 132 because it introduces new matter into the disclosure. 35 U.S.C. 132 states that no amendment shall introduce new matter into the disclosure of the invention. The added material which is not supported by the original disclosure is as follows: the new upper limit of 150 nm (claim 18) in particle size of the claimed titania particles. Neither is there support for an upper limit of 125 nm (claim 19). Although there is support for 100 nm and 500 nm, there is no support for 150 nm or 125 nm as the upper limit.

Applicant is required to cancel the new matter in the reply to this Office Action.

2. New Issue:

The newly amended claims 18, 19 and 30 raise new issue. The new limitation of particle size of not more than 150 nm, requires new search and consideration and thus raises new issue. In addition, in claim 18, the term "no more than about 150 nm" is indefinite because while the phrase "no more than" precludes the value of 150 nm and any value above it, the term "about" includes the value of 150 nm and values

up to 10% above 150 nm. This is a question under 112, second paragraph and thus raises new issue.

Response to Arguments

3. Claims 18-30 are rejected under 35 U.S.C. 102(b) as being anticipated by Wiederhoft et al (US 5,840,111) as set forth in previous office actions and further discussed below.

Applicants argued that the sol-gel process taught by Wiederhoft does not yield rutile titanium dioxide citing the reference "Surface and bulk characterization of titanium-oxo clusters and nanosized titania particles through O solid state NMR" by Scolan et al ("Scolan reference") as support. The sol-gel process in this reference is based on growth hydrolysis and condensations reactions of metallo-organic compounds in particular metal alkoxides. This process is stated in the Wiederhoft as undesirable because of known disadvantages (see Wiederhoft, col. 1, line 46 to col. 2, line 11). Therefore, the titanium dioxide particles produced by the process taught by Wiederhoft are not the same product produced by the process taught in the Scolan reference cited by Applicants. Thus, anatase particles are not the only resulting particles as argued.

Not all sol-gel processes are created equal. In fact, there are two major differences between the sol-gel process taught by Scolan and sol-gel process by Wiederhoft. First, Wiederhoft process is a *non*-hydrolytic sol/gel process as opposed

to the hydrolytic sol/gel process taught in the Scolan reference. Secondly, the main reactants in the Wiederhoft process involve NO organic compounds while the process taught by Scolan is based on an organic compound (i.e. a metal alkoxide).

In addition, the titanium dioxide particles in the Wiederhoft reference are produced by the sulphate process which is known to yield <u>rutile</u> titanium dioxide (see Wiederhoft, col. 2, lines 29-30 and col. 3, lines 32-36).

Therefore, contrary to applicants' argument, the titanium dioxide particles disclosed in the Wiederhoft reference comprise rutile titanium dioxide.

4. Claims 18-21 and 23-28 are rejected under 35 U.S.C. 102(b) as being anticipated by Montino et al (US 4,803,064) or Colombo et al (US 3,661,522) as set forth in the last office action and further discussed below.

Applicants' arguments with regard to the rejections based on these two references are relied solely on the newly added limitation "particle size of up to 150 nm/125 nm". Such arguments are moot because the amendment has not been entered and will not be entered because it raises new matter and new issue as discussed under the section "Response to Amendment" above.

- 5. To simplify the issues, all rejections of obviousness under 35 U.S.C. 103 are hereby withdrawn.
- 6. Applicant's arguments filed February 17, 2003 have been fully considered but they are not persuasive for the reasons set forth above.

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to H. T. Le whose telephone number is 703-308-2415. The examiner can normally be reached on 10:00 a.m. to 7:30 p.m., Mondays to Friday.

The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9610 for regular and After Final communications.

H. T. Le

Primary Examiner Art Unit 1773

hl March 3, 2003